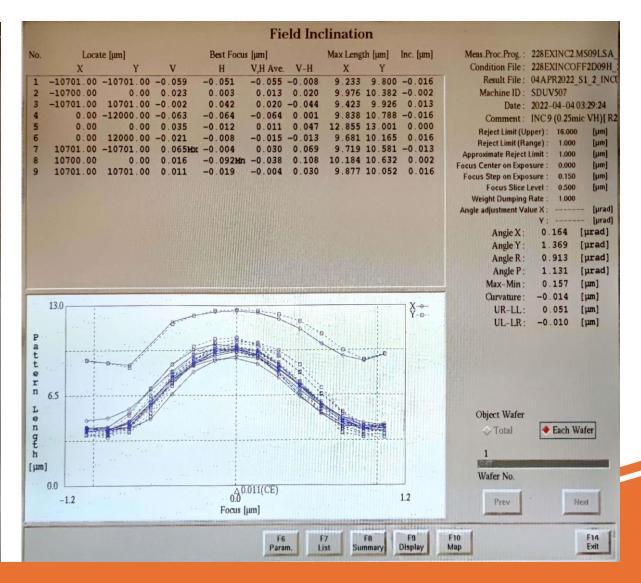
SDUV-507

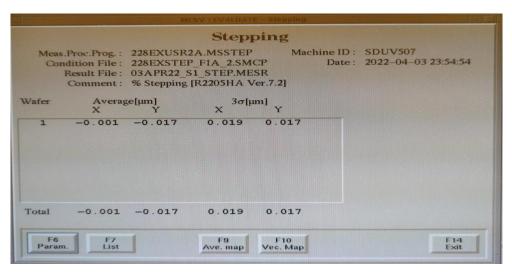
Best Focus

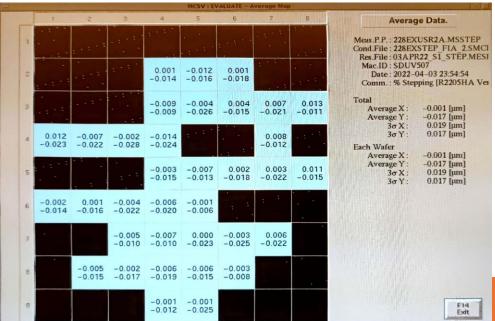
Best Focus Max Length [1m] Meas.Proc.Prog.: 228EXUSR2M.MSBSTL Best Focus [µm] Locate [µm] V.H Ave. V-H Condition File: 228EXBSTD 2.SMCP Result File: 03APR22 S1 BST.MES 0.066Mx 0.031Mn 0.048 0.035 12.134 12.572 Machine ID: SDUV507 Date: 2022-04-03 23:46:07 Comment: Best focus (0.25mic)[R2 Reject Limit (Upper): Reject Limit (Range): Approximate Reject Limit: Focus Center on Exposure: 0.000 Focus Step on Exposure: 0.150 Focus Slice Level: 0.500 Weight Dumping Rate: 1.000 Angle adjustment Value X: -----0.035 [µm] 13.0 Object Wafer 9 n * Each Wafer ◆ Total [µm] Wafer No. -1.4Prev Next Focus [µm] Exit

Field Inclination

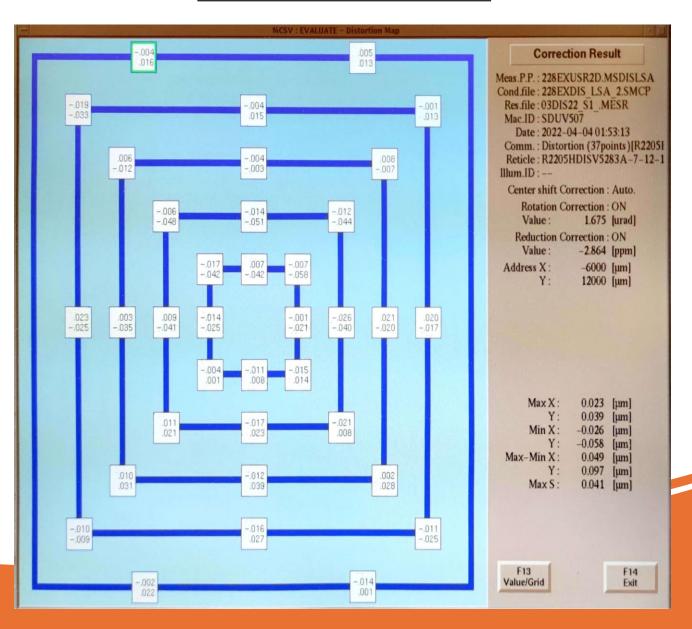


Stepping Accuracy





Lens Distortion



Illumination Uniformity ID1

MCSV: EVALUATE - Lamp Map **Illumination Uniformity** Res.File: 02NOV2022 TF ID1.I.AMP Mac.ID: SDUV507 Date: 2022-11-02 15:27:06 Comm.: LAMP Illumination Unifo Illumination ID 1000.000 Maximum 824.637 883.228 Average: Uniformity: 9.611 [%] 38.273 [mW/cm²] Intra-field Repeat Count 841 Intra-field Repeat No. 835 Disp. Mode 832 838 891.2 Detail 889.2 887.2 Summary 885.2 883.2 3D 881.2 879.2 877.2 875.2 884 889 Exit

Illumination Uniformity ID6

